

ABSTRACT OF THE DISCLOSURE

It is disclosed a method of forming fine patterns comprising: covering a substrate having photoresist patterns
5 with an over-coating agent for forming fine patterns, applying heat treatment to cause thermal shrinkage of the over-coating agent so that the spacing between adjacent photoresist patterns is lessened by the resulting thermal shrinking action, and removing the over-coating agent substantially
10 completely by way of bringing thusly treated substrate into contact with a remover solution for over 60 seconds.